Interview Summary	Application No.	Applicant(s)		
	10/735,769	KAWAMURA ET	KAWAMURA ET AL.	
	Examiner	Art Unit		
	Daborah Chacko-Davis	1756		
All participants (applicant, applicant's representative, PTO personnel):				
(1) <u>Ms. Jennifer M. Hayes, Reg. No. 40,641</u> .	(3) <u>Daborah Chacko-Davi</u>	<u>s</u> .		
(2) Ms. Nyeemah Grazier.	(4)			
Date of Interview: 26 July 2007.				
Type: a)☐ Telephonic b)☐ Video Conference c)☑ Personal [copy given to: 1)☐ applicant 2	r)⊠ applicant's representativ	e]		
Exhibit shown or demonstration conducted: d) Yes If Yes, brief description: An Illustration of the difference al., and that of the applicant's claimed invention.	e)⊡ No. <i>between the substrate and i</i>	nitiating layer of K	awamura et	
Claim(s) discussed: <u>1, and 14</u> .			٠	
Identification of prior art discussed: <u>U. S. Patent No. 6,919</u> ,	158 (Kawamura et al).			
Agreement with respect to the claims f) was reached. g	)⊠ was not reached. h)□ l	N/A.		
Substance of Interview including description of the general reached, or any other comments: <u>See Continuation Sheet</u> .	nature of what was agreed to	o if an agreement	was	
(A fuller description, if necessary, and a copy of the amendallowable, if available, must be attached. Also, where no callowable is available, a summary thereof must be attached	opy of the amendments that	greed would rende would render the c	r the claims claims	
THE FORMAL WRITTEN REPLY TO THE LAST OFFICE A INTERVIEW. (See MPEP Section 713.04). If a reply to the GIVEN A NON-EXTENDABLE PERIOD OF THE LONGER INTERVIEW DATE, OR THE MAILING DATE OF THIS INTIFILE A STATEMENT OF THE SUBSTANCE OF THE INTERPREPARENTS ON REVERSE SIDE OF THE STATEMENT.	last Office action has already OF ONE MONTH OR THIRT ERVIEW SUMMARY FORM,	y been filed, APPL Y DAYS FROM TI WHICHEVER IS	ICANT IS HIS	
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	The state of the s			
Examiner Note: You must sign this form unless it is an Attachment to a signed Office action.	Examiner's sign	nature, if required	<del></del>	

Continuation of Substance of Interview including description of the general nature of what was agreed to if an agreement was reached, or any other comments: It was discussed that the pattern forming method (in accordance to the illustration and the instant specification) involves the use of a substrate wherein the initiator is fixed throughout the whole area of the substrate and then image-wise exposed to light to inactivate the polymerization-initiating ability of the initiator in the exposed region alone which is different than that of the pattern formation of Kawamura i.e., Kawamura teaches that the exposed region initiates the species to activate polymerization activity.